"Investigation of etching and deposition processes of Cl2/O2/Ar inductively coupled plasmas on silicon by means of plasmasurface simulations and experiments". Tinck S, Boullart W, Bogaerts A, Journal of physics: D: applied physics **42**, 095204 (2009). http://doi.org/10.1088/0022-3727/42/9/095204

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